

	Sulfuric acid	Ascorbic acid	Fluorine ion (HF)	Cerium abrasive agent	Result
Sample 1	4% by weight	1% by weight	200 ppm	Not detected	o
Sample 2	4% by weight	1% by weight	500 ppm	Not detected	□
Sample 3	4% by weight	1% by weight	1000 ppm	Not detected	□
Comparative example 1	4% by weight	1% by weight	0.50 % (H ₂ SiF ₆)	Detected	x
Comparative example 2	4% by weight	1% by weight	0.30 % (H ₂ SiF ₆)	Detected	x
Comparative example 3	4% by weight	1% by weight	10 ppm	Detected	□
Comparative example 4	4% by weight	1% by weight	50 ppm	Detected	x

FIG 1

HF etching speed by SAM resist

Fluorine ion concentration (ppm)	1	10	30	100	200	250	300	1000
Maximum value				0.61	2.40		5.55	62.86
Average value	0.01	0.03	0.07	0.54	2.40	5.90	5.55	45.65
Minimum value				0.46	2.40		5.55	36.07
Target value	3.64	3.64	3.64	3.64	3.64	3.64	3.64	3.64

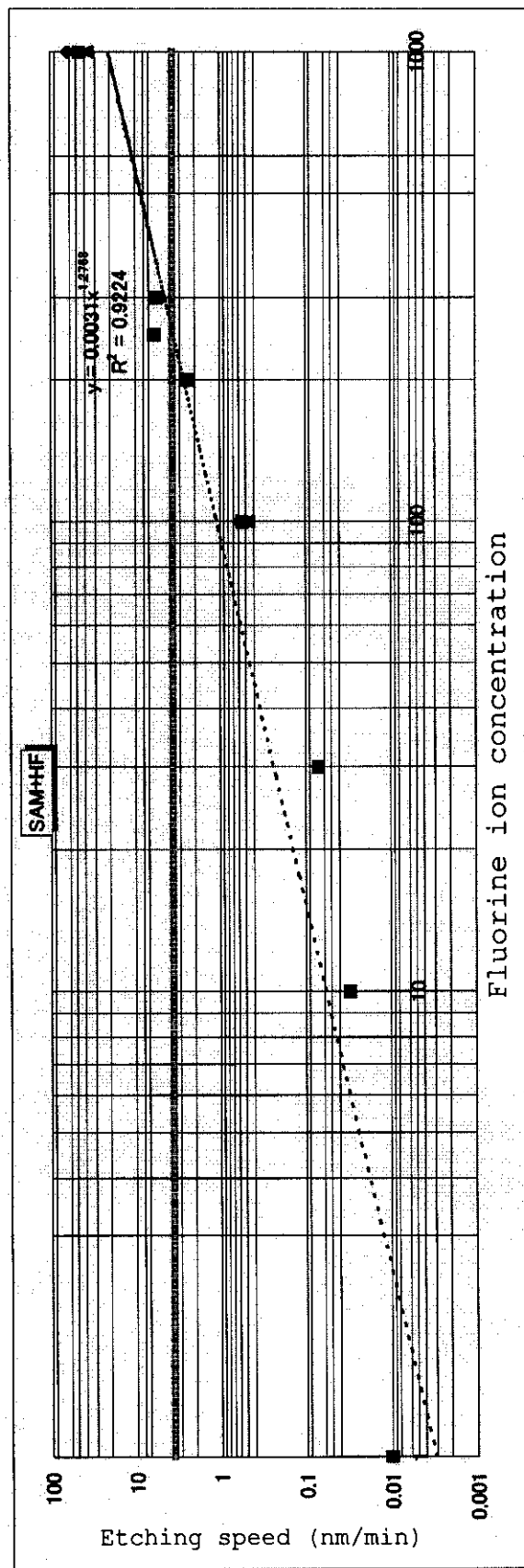


FIG. 2